L Number	Hits	Search Text	DB	Time stamp
1	7472	430/30 or 257/273 or 714/724	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/04 17:16
2	5786600	photolithography system	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/04 17:16
3	72481	photolithography tool and (stage with semiconductor wafer near1 mounted)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/04 17:18
4	2480858	pre-determined image	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/04 17:19
5	371569	mov$3 near1 stage with automatically focus near1 pre-determined image near5 semiconductor wafer	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/04 17:21
6	21003	(pre-determined image) and (photolithography tool and (stage with semiconductor wafer near1 mounted))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/04 17:21
7	20901	(photolithography system) and ((pre-determined image) and (photolithography tool and (stage with semiconductor wafer near1 mounted)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/04 17:21
8	792	(mov$3 near1 stage with automatically focus near1 pre-determined image near5 semiconductor wafer) and ((photolithography system) and ((pre-determined image) and (photolithography tool and (stage with semiconductor wafer near1 mounted))))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/04 17:22
9	8	(430/30 or 257/273 or 714/724) and ((mov$3 near1 stage with automatically focus near1 pre-determined image near5 semiconductor wafer) and ((photolithography system) and ((pre-determined image) and (photolithography tool and (stage with semiconductor wafer near1 mounted)))))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/04 17:23
10	1575547	automation host computer	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/04 17:26
11	831	poll$3 and (photolithography tool with data near2 logged movement near2 stage)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/04 17:27
13	26277	(automation host computer) and (analyz$3 near1 data)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/04 17:30
14	1127027	compar$3 and (data with predetermined error condition$1)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/04 17:29

15	17855	((automation host computer) and (analyz$3 near1 data)) and (compar$3 and (data with predetermined error condition$1))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/04 17:29
17	4	(((automation host computer) and (analyz$3 near1 data)) and (compar$3 and (data with predetermined error condition$1))) and ((mov$3 near1 stage with automatically focus near1 pre-determined image near5 semiconductor wafer) and ((photolithography system) and ((pre-determined image) and (photolithography tool and (stage with semiconductor wafer near1 mounted)))))	USPAT	2004/08/04 17:31

L Number	Hits	Search Text	DB	Time stamp
1	7472	430/30 or 257/273 or 714/724	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/04 17:16
2	5786600	photolithography system	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/04 17:16
3	72481	photolithography tool and (stage with semiconductor wafer near1 mounted)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/04 17:18
4	2480858	pre-determined image	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/04 17:19
5	371569	mov$3 near1 stage with automatically focus near1 pre-determined image near5 semiconductor wafer	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/04 17:21
6	21003	(pre-determined image) and (photolithography tool and (stage with semiconductor wafer near1 mounted))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/04 17:21
7	20901	(photolithography system) and ((pre-determined image) and (photolithography tool and (stage with semiconductor wafer near1 mounted)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/04 17:21
8	792	(mov$3 near1 stage with automatically focus near1 pre-determined image near5 semiconductor wafer) and ((photolithography system) and ((pre-determined image) and (photolithography tool and (stage with semiconductor wafer near1 mounted))))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/04 17:22
10	1575547	automation host computer	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/04 17:26
11	831	poll$3 and (photolithography tool with data near2 logged movement near2 stage)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/04 17:27
13	26277	(automation host computer) and (analyz$3 near1 data)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/04 17:30
14	1127027	compar$3 and (data with predetermined error condition$1)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/04 17:29
15	17855	((automation host computer) and (analyz$3 near1 data)) and (compar$3 and (data with predetermined error condition$1))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/04 17:29

17	4	(((automation host computer) and (analyz$3 near1 data)) and (compar$3 and (data with predetermined error condition$1))) and ((mov$3 near1 stage with automatically focus near1 pre-determined image near5 semiconductor wafer) and ((photolithography system) and ((pre-determined image) and (photolithography tool and (stage with semiconductor wafer near1 mounted)))))	USPAT	2004/08/04 17:47
9	8	(430/30 or 257/273 or 714/724) and ((mov$3 near1 stage with automatically focus near1 pre-determined image near5 semiconductor wafer) and ((photolithography system) and ((pre-determined image) and (photolithography tool and (stage with semiconductor wafer near1 mounted)))))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/04 17:54
18	21689	355/? or 430/? or 359/?	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/04 17:55
19	4	(355/? or 430/? or 359/?) and ((430/30 or 257/273 or 714/724) and ((mov$3 near1 stage with automatically focus near1 pre-determined image near5 semiconductor wafer) and ((photolithography system) and ((pre-determined image) and (photolithography tool and (stage with semiconductor wafer near1 mounted))))))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/04 17:56
20	4	(355/? or 430/? or 359/?) and ((355/? or 430/? or 359/?) and ((430/30 or 257/273 or 714/724) and ((mov$3 near1 stage with automatically focus near1 pre-determined image near5 semiconductor wafer) and ((photolithography system) and ((pre-determined image) and (photolithography tool and (stage with semiconductor wafer near1 mounted)))))))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/04 17:57
21	880	(355/? or 430/? or 359/?) and (430/30 or 257/273 or 714/724)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/04 17:57
22	4	((355/? or 430/? or 359/?) and (430/30 or 257/273 or 714/724)) and ((mov$3 near1 stage with automatically focus near1 pre-determined image near5 semiconductor wafer) and ((photolithography system) and ((pre-determined image) and (photolithography tool and (stage with semiconductor wafer near1 mounted)))))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/04 17:58